

ALPIN Workshop 2022, Fraunhofer-inHaus-Zentrum, Duisburg

Time (hrs)	Agenda - Monday, 12.09.2022
Starting 13.00	Arrival, Registration and Refreshments
14.00 - 14.25	A. Devi, A. Grabmaier, M. Knaut, M. Michel Welcome address and introduction
14.25 - 14.35	M. Michel (<i>Fraunhofer IMS</i>) Overview of Fraunhofer IMS's ALD project activities
14.35 - 14.50	J. Koch (<i>Dockweiler Chemicals</i>) Dockweiler Chemicals – Passion for Chemistry
14.50 - 15.05	X. Hu (<i>TU Chemnitz</i>) Reverse engineering of thermal Cu ALE: an ab initio study
15.05 - 15.20	Nils Boysen (<i>Ruhr-Universität Bochum</i>) New precursor chemistries for metals
15.20 - 15.45	Break and poster session
15.45 - 16.00	F. Eweiner (<i>Heraeus</i>) Closing the Loop on Ruthenium: Precious Metal Deposition Precursors and Recycling
16.00 - 16.15	M. Ziegler (<i>Leibniz IPHT</i>) Broadband absorbers made by ALD
16.15 - 16.30	M. Franz (<i>Fraunhofer ENAS</i>) ALD of metallic Cobalt
16.30 - 16.45	C. Hossbach (<i>Picosun</i>) ALD of ruthenium using a zero-valent precursor
16.45 - 17.15	Break and poster session
17.15 - 17.30	J. Cipo (<i>Fraunhofer ISIT</i>) Powder MEMS-Technologie
17.30 - 18.15	M. Michel (<i>Fraunhofer IMS</i>) Virtual and interactive lab tour through the microsystems technology cleanroom of Fraunhofer IMS
starting 19.00	Dinner in Restaurant Mezzomar Bertaallee 7, 47055 Duisburg, Tel.: 0203 39 308 90

Time (hrs)	Agenda - Monday, 13.09.2022
09.00 - 09.10	A. Devi (Ruhr-Universität Bochum) Welcome and overview of ALD related research activities at RUB
09.10 - 09.30	David Muñoz-Rojas (LMGP) Exploiting the unique opportunities offered by close-proximity SALD
09.30 - 09.45	K. Niiranen (Beneq) Industrial advanced ALD applications at Beneq
09.45 - 10.00	F. Krahl (Leibniz IFW) ALD of layered metal chalcogenides
10.00 - 10.15	R. Neubieser (Fraunhofer IMS) Gas detection sensor based on ALD-MoS ₂
10.15 - 10.30	D. Schlamm (Sempa) SEMPA - ALD/ALE related Projects
10.30 - 11.00	Break and poster session
11.00 - 11.15	J. Zessin (Sentech) Advances in atomic layer processing utilizing in-situ real time ellipsometry
11.15 - 11.30	C. Bock (Ruhr-Universität Bochum) Detailed analysis of plasma etching processes of large-area ALD grown MoS ₂
11.30 - 11.45	F. Beyer (Fraunhofer IISB) Low Damage etching of nitride semiconductors
11.45 - 12.15	Break and poster session
12.15 - 12.30	H. Bryja (Firma FHR) ALD process optimization with quartz crystal microbalance using Al:ZnO as an example
12.30 - 12.45	M. Knaut (TU Dresden) Flash-lamp enabled atomic layer deposition
12.45 - 13.00	L. Demelius (TU Graz) Combining initiated chemical vapor deposition and plasma-enhanced atomic layer deposition: a study of initial growth and interface formation
starting 13.00	Concluding Remarks and Departure